Spartan felt Company

PORETEX 2LN™ POLISHING PADS

In the surface preparation process, there is a need to produce ultra polished surfaces with synthetic pads. Spartan's suede polishing material is designed to generate final polished surfaces using sub-micron slurries. It's "low nap/small pore" composition retains the polishing vehicle on the exposed pad surface allowing for better polished surface quality and lower surface tension to the wafers being polished. While our **Poretex 1™** material is best suited for glass, **Poretex 2LN™** is excellent for semiconductor and compound semiconductor wafers, quartz, sapphire, silicon carbide and various crystals. These pads are designed to work best with colloidal silica, sodium hydroxide, cerium and alumina slurries over a wide range of pH and slurry concentration mixtures.

Poretex 2LN™ Pads are available in plain, embossed or textured front surfaces. Pressure sensitive adhesive is standard for use with a wide pH slurry range. Material can be ordered in roll form or pre-cut pad diameters upon request.

TECHNICAL SPECIFICATIONS:

THICKNESS (mm): 1.37 +/- 0.10	WEIGHT: (g/m2): 570 +/- 50
DENSITY (g/m3): 0.42 +/-0.05	COMPRESSION: 4.5 +/- 2.0%
HARDNESS (Shore C): 64 +/- 5	NAP LAYER THICKNESS: 450 +/- 80µ
PORE SIZE: 60 +/- 20µ	RECOVERY: 63 +/- 15%

Spartan Polishing Pads are a cost effective choice for precision final polishing. Attention to customer service needs and quality control procedures are a priority with us. Please call us today with your final polishing requirements.

SALEM
Advanced Surfacing Materials

1 800-234-1982